UNITED STATES PATENT AND TRADEMARK OFFICE

Bib Data Sheet

CONFIRMATION NO. 5111

SERIAL NUMBER 10/620,426	FILING OR 371(c) DATE 07/17/2003 RULE	CLASS 438	GROUP ART UNIT 2823	ATTORNEY DOCKET NO. MI22-2360

APPLICANTS

Sujit Sharan, Boise, ID;
Gurtej S. Sandhu, Boise, ID;

T. D

** CONTINUING DATA ***************************
This application is a CON of 09/652,534 08/31/2000 ABN
** FOREIGN APPLICATIONS ********************
none

IF REQUIRED, FOREIGN FILING LICENSE GRANTED **
10/17/2003

Foreign Priority claimed ☐ yes ☒ no		STATE OR COUNTRY ID	SHEETS DRAWING 4	TOTAL CLAIMS 35	INDEPENDENT CLAIMS 7
35 USC 119 (a-d) conditions met ☐ yes ☒ no ☐ Met after Allowance					
Verified and Acknowledged _Tuuly Dang_ Examiner's Signature ___ Initials					

ADDRESS
21567

TITLE
Plasma enhanced chemical vapor deposition methods and semiconductor processing methods of forming layers and shallow trench isolation regions

FILING FEE RECEIVED 1356	FEES: Authority has been given in Paper No. _____ to charge/credit DEPOSIT ACCOUNT No. _____ for following:	☐ All Fees
		☐ 1.16 Fees (Filing)
		☐ 1.17 Fees (Processing Ext. of time)
		☐ 1.18 Fees (Issue)
		☐ Other _____
		☐ Credit